Homework-3 AV221-Semiconductor Devices

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Derive the expression for the built-in rollage of p-ndiode.

Built-in voltage, $v_{bi} = |\Delta v_{fp}| + |\Delta v_{fn}|$ Using $n_o = n_i \exp\left(\frac{E_f - E_{fi}}{kT}\right)$

and, ▲ eav_{fp}= E_{fi}-E_f eav_{fn}= E_f-E_{fi}

Similarly,

:.
$$V_{bi} = \frac{KT}{e} \ln \left(\frac{m_0 p_0}{n_1 i^2} \right)$$

Take $n_0 = N_D \notin p_0 = N_A$, $e = q$

$$\Rightarrow V_{bi} = \frac{KT}{q} \ln \left(\frac{N_A N_A}{n_1 i^2} \right)$$

2 Derive the expression for the depletion widths along n-sider and p-sider of p-n junction.

3

5dn: Poisson's equ for one-dimensional analysis:

 $\frac{d^2 \phi(x)}{dx^2} = -\frac{f(x)}{\epsilon_s} = -\frac{dE(x)}{dx}, \quad \phi(x) : \text{ Electric field } \text{ Potential }$

f(n): Electric fless
f(n): volume charge density.

Es: permittivity of semiconductor

$$f(x) = -eNA$$
, $-xp < x < D$
 $f(x) = eND$, $0 < x < Xn$

Electric field for p-region.

Smilarly for n- Hegion,

By D and (1),

Potential in p-region,

As
$$V_1(x) = 0$$
 at $x = -3(p \Rightarrow c_2 = \frac{eNA}{2Es}x_p^2$

Potential in n-region,

$$\frac{V_2(x) = \int \frac{e^{ND}}{E_s} \left(x_n - x_1 dx = \frac{e^{ND}}{E_s} \left(x_n x - \frac{x^2}{2} \right) + c_s}{\left(x_n x - \frac{x^2}{2} \right)}$$

As
$$V_2(x)=0$$
 at $x=0 \Rightarrow V_1(x)=V_2(x) \Rightarrow G=C_2$

At
$$x = x_n$$
, $v_2(x_1 = v_b)$

$$\Rightarrow v_{bi} = \frac{e}{2\epsilon_s} \left(N_D x_n^2 + N_A x_p^2 \right) - (iii)$$

Using (ii) $4(iii)$,
$$v_{bi} = \frac{e}{2\epsilon_s} \left(N_D \frac{x_p^2 N_A^2}{N_D^2} + N_A x_p^2 \right)$$

$$\Rightarrow x_p^2 = 2\epsilon_s \frac{v_b}{e} \left(\frac{N_A^2 + N_A}{N_D} + \frac{2\epsilon_s v_{bi}}{N_A} \frac{N_B}{N_A} \left(\frac{1}{N_A + N_D} \right) \right)$$

Similarly,
$$x_n = \sqrt{2\epsilon_s v_{bi}} \cdot \frac{N_A}{N_D} \left(\frac{1}{N_A + N_D} \right)$$

3 Setting stating all the assumptions, derive the shockley diode equation.

$$V_{bi} = \frac{kT}{9} \ln \left(\frac{N_A N_D}{\gamma_{i}^2} \right)$$

Assuming complete ionization, nno ND, Nn ~ Pro.

Applying fortward voltage V, Vbi - Vbi - V, $n_p = n_{n_0} \exp\left(-\frac{eVbi}{kT}\right)^{-1} = n_{n_0} \exp\left(-\frac{eVbi}{kT}\right) \exp\left(\frac{eV}{kT}\right)$

⇒ np=npo exp(ev), nno ≈ constant for low-level injection. Similarly for holes,

Po ____

P

Using continuity eqn, dhe - Pr wat - up & dh + sp de Pr + Sip - Pr-Pro. At steady state din =0 F=0 for no electric field applied. Gin= o for reo generation => de Profet = Pro-mo => Pn-mo = k1 exp (-xc) + k2 Applying boundary conditions, At x= m, Pn (m) = Pno exp (qv) At x(-)00, Pn (00)= Pno. X=Mn => Pro exp(QN)-Pro= K1 exp (-X) => KI= Pno (exp (AV) -1 (exp (Xn) :. Pn(x) = Pno + Pno (exp(av)-1] exp (xn-x). Now, Jp= -9.Dp dkn(x) = -9Dp Pno Fext (2V)-1]exp (2n-x) (-1) | x=1/n = -9 Pp. Pno exp(2V)-1]. Similarly, Jn= -9 Dn. npo [exp(qv)-1]. : Itotal = I = Ip + In = [exp {av } -1] [QA (Dp. Pno + Dn npo) Ln : [I = Io [exp(av)-1]].